

ABSTRACT

TWO-COMPONENT SILICON WAFER CLEANING AGENT AND CLEANING METHOD

Disclosed are a two-component silicon wafer cleaning agent and a cleaning method, which are used for manufacturing a silicon solar cell and belong to the technical field of solar cell production. The cleaning agent in the present disclosure comprises a component A and a component B, wherein the component A comprises the following components in percentage by weight: 5-10% of an inorganic base, 0.5-1.5% of an organic base, 4-8% of a dispersant, 3-5% of an oxidation inhibitor and the balance of water; and the component B comprises the following components in percentage by weight: 12-15% of an alcohol ether solvent and the balance of water. By selecting the components of the cleaning agent, the cleaning yield is significantly improved. Moreover, the hydrogen peroxide tank commonly used in the cleaning process is not used, so that the safety of the cleaning process is improved.

[No Figure]